

Figure 1. Simplified process flow in RMG

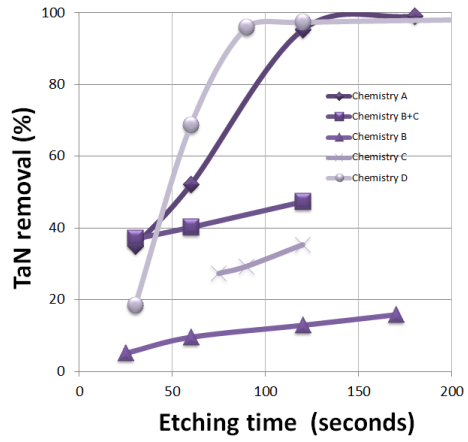


Figure 2. TaN removal by different etch chemistry

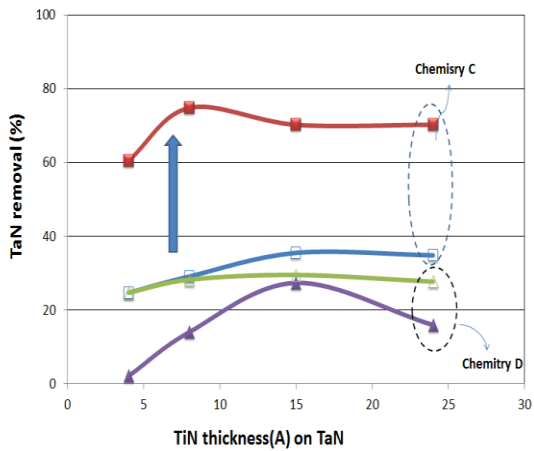


Figure 3. RIE effects on TaN removal rate in TiN/TaN stack

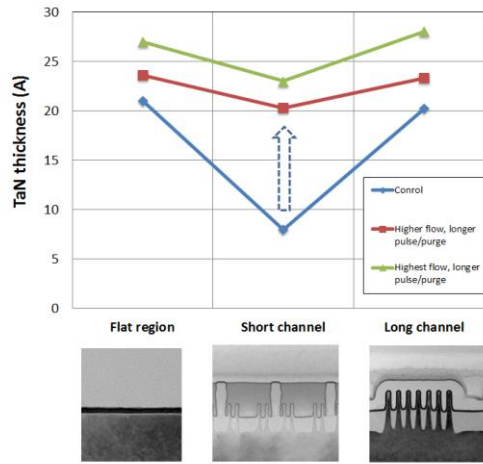


Figure 4. TaN loading effects on different macros

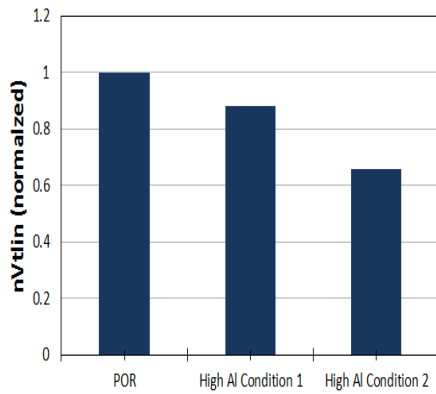


Figure 5. Normalized nVttn with different nWF process.

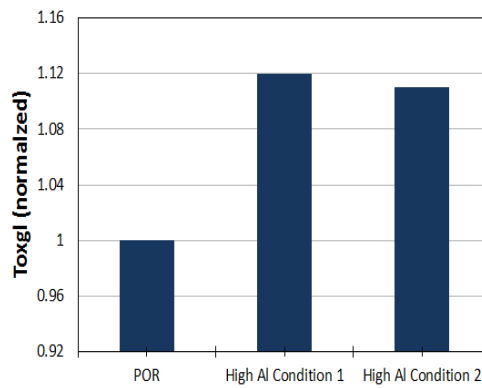


Figure 6. Normalize Toxgl gain from different nWF process.